

## THE INFLUENCE OF NiFe THICKNESS OF TOP-ELECTRODE ON EXCHANGE COUPLING PARAMETERS OF IrMn<sub>3</sub> BASED MTJ

T. Stobiecki<sup>1,2</sup>, Cheol Gi Kim<sup>1</sup>, Chong-Oh Kim<sup>1</sup>, Yongkang Hu<sup>1</sup>, J. Wrona<sup>2</sup>, J. Kanak<sup>2</sup>, M. Tsunoda<sup>3</sup>, M. Takahashi<sup>3</sup>

<sup>1</sup>Chungnam National University, Department of Materials Engineering, Daejeon, 305-764, Korea; <sup>2</sup>University of Mining and Metallurgy, Department of Electronics, 30-059 Krakow, Poland; <sup>3</sup>Tohoku University, Department of Electronic Engineering, Sendai 980-8579, Japan

Recent works of IrMn<sub>3</sub> based MTJ's have focused mainly on enhancement of TMR ratio, by modifying the preparation conditions of tunnel barrier [1], or local electrical properties [2]. There are only a few reports which discuss interlayer exchange coupling between two ferromagnetic electrodes [3]. In this work particular attention will be paid to the evolution of the interlayer exchange coupling with the thickness of NiFe and annealing in junctions with the structure: of Ta(50Å)/Cu(100Å)/Ta(50Å)/NiFe(20Å)/Cu(50Å)/IrMn(100Å)/CoFe(25Å)/Al-O/CoFe(25Å)/NiFe(t)/Ta(50Å), where  $t = 0\text{Å}, 100\text{Å}, 300\text{Å}, 600\text{Å}$  and  $1000\text{Å}$ . We obtained decrease of minor loop shifting field ( $H_{ua}$ ) and coercivity ( $H_c$ ) for free layer with increasing NiFe thickness in as-deposited and annealed samples. For example the unidirectional anisotropy field  $H_{ua} = 8$  [Oe] and  $H_c = 14$  [Oe] for as-deposited junction with  $t = 100\text{Å}$ . After annealing at  $300^\circ\text{C}$  in external field 1 [kOe], we obtained following values: TMR = 40%,  $H_{ua} = 11.5$  [Oe],  $H_c = 11.6$  [Oe] for free layer and exchange biased field of pinned layer,  $H_{EB} = 1440$  [Oe] which corresponds to exchange biased energy  $E_{EB} = 0.52$  erg/cm<sup>2</sup>. The variations of  $H_c$  and  $H_{ua}$  correlate with the size of NiFe grains determined from GID-XRD measurements. The analysis of the surface roughness, determined from AFM measurements, of bottom CoFe electrode layer and the distribution of  $H_{ua}$  (obtained from micro-MOKE, M-H loop tracer) across the junction, suggests that variation of the interlayer exchange coupling field of the free layer is well described by dipole interactions in the form of so-called Néel "orange peel" coupling.

[1] M.Tsunoda et al. Appl. Phys. Lett. **80** (2002), 3135

[2] Y.Ando et al. J. Magn. Magn. Mat. **226-230** (2001), 924

[3] K.Li et al. J. Magn. Magn. Mat. **241** (2002), 89